

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant	:	Yamazaki et al.
Appl. No.	:	10/566,425
Filed	:	January 30, 2006
For	:	POSITIVE PHOTORESIST COMPOSITION AND METHOD OF FORMING RESIST PATTERN
Examiner	:	Chu, John S Y
Group Art Unit	:	1795

**RESPONSE TO RESTRICTION REQUIREMENT****Mail Stop Amendment**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

In the Restriction Requirement mailed **May 19, 2008**, the Examiner divided the claims into two patentable distinct inventions:

I. Claims 1-10 and 13-23, drawn to a photoresist composition, classified in class 430, subclass 170; and

II. Claims 11, 12, 24, and 25, drawn to a method of use, classified in class 430, subclass 326.

In response to the Restriction Requirement, Applicants hereby elect Group I, claims 1-10 and 13-23, without traverse. Although claims 11, 12, 24, and 25 are directed to a non-elected invention, inasmuch as these claims are all ultimately dependent on the elected claims, rejoinder of the claims will be proper upon allowance of the elected claims.

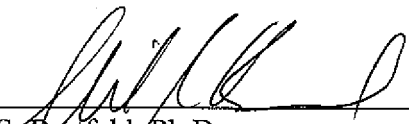
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No fees are believed to be due. However, please charge any fees, including any fees for extensions of time, or credit overpayment to Deposit Account No. 11-1410.

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: 6/4/08

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